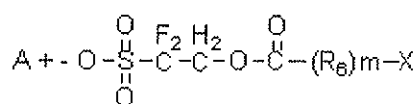


ABSTRACT

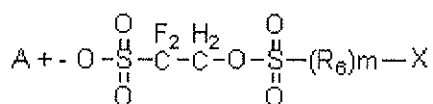
ACID GENERATING AGENT FOR CHEMICALLY AMPLIFIED RESIST COMPOSITIONS

There is provided an acid generating agent represented by the following formula (1) or (2), which is included in chemically amplified resist compositions:

[Formula 1]



[Formula 2]



When compared to those photo-acid generating agents based on an anion having a bulky alicyclic ring, and those photo-acid generating agents having relative short chains and having hydrophobic characteristics, such as the existing trifluoromethanesulfonate or nonafluorobutanesulfonate type agents, the acid generating agent according to the present invention has intermediate physical properties in terms of diffusion rate or dispersibility, and thus is advantageous in controlling the diffusion rate and the degree of dispersion upon realizing resists with high resolution.

Figure 3